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Sender:

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Subject Matter:

US Patent Application Number: 10/707,968

Renewed Petition Under 37 CFR 1.182

Total Pages (including cover sheet): 8 pages

Attachments:

- 1) Certificate of Transmission
- 2) Transmittal Form
- 3) Renewed Petition Under 37CFR 1.182
- 4) Copy of Application Data Sheet Exhibit A
- 5) Copy of Page 1 of Specification (Electronic Version) Exhibit B

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- 1) Transmittal Form
- 2) Renewed Petition Under 37CFR 1.182
- 3) Copy of Application Data Sheet Exhibit A
- 4) Copy of Page 1 of Specification (Electronic Version) Exhibit B

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Approved for use through 07/31/2006, OMB 0851-0031
U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE
Under the Paperwork Reduction Act of 1995, no reasons are required to respond to a collection of information unless it displays 8 yalid OMB control number. Application Number 10/707.988 January 29, 2004 Filing Date TRANSMITTAL First Named Inventor Dominique MANGELINCK FORM Art Unit 2811 Examiner Name Not Assigned Yet (to be used for all correspondence after initial filing) Attorney Docket Number ASTAP2004-01 Total Number of Pages in This Submission **ENCLOSURES** (Check all that apply) After Allowance Communication to TC Drawing(s) Fee Transmittal Form Appeal Communication to Board Licensing-related Papers of Appeals and Interferences Fee Attached Appeal Communication to TC (Appeal Notice, Brief, Reply Brief) Petition Amendment/Reply Petition to Convert to a Proprietary Information After Final Provisional Application Power of Attorney, Revocation Status Letter Change of Correspondence Address Affidavits/declaration(s) Other Enclosure(s) (please Identify Terminal Disclaimer Extension of Time Request below): Request for Refund Express Abandonment Request CD, Number of CD(s) _ Information Disclosure Statement Landscape Table on CD Certified Copy of Priority Remarks Document(s) 1) Renewed Petition Under 37CFR 1.182 2) Copy of Application Data Sheet - Exhibit A Reply to Missing Parts/ 3) Copy of Page 1 of Specification (Electronic Version) - Exhibit B Incomplete Application Reply to Missing Parts under 37 CFR 1,52 or 1.53 SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT Firm Name IP Pte Ltd Horizoi Signature Printed name CHIN Date Reg. No. November 12, 2004 38,842 CERTIFICATE OF TRANSMISSION/MAILING I hereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United State envelope addressed to Commissioner for Cateria. Co. Dox 1900 Alexandria, VAZZ 19-1900 on the date shown below: Signature Mende Date Wendy LIM November 12, 2004 Typed or printed name

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Appl. No.: 10/707,968

Renewed Petition under 37 CFR 1.182, dated November 12, 2004

Response to Decision of September 21, 2004

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.

: 10/707,968

Confirmation No.

: 1967

Applicant

: Dominique MANGELINCK

et al.

Filed

: January 29, 2004

TC / A.U.

: 2811

Examiner

: Not Assigned Yet

Docket No.

: ASTAP2004-01

Customer No.

: 031366

Title

: Gate Electrodes and the Formation Thereof

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Commissioner for Patents Office of PCT Legal Administration P.O. Box 1450 Alexandria, Virginia 22313-1450

Renewed Petition Under 37 CFR 1.182

Sir:

In response to the Decision mailed on September 21, 2004 (Decision) in the aboveidentified application, Applicants respectfully request reconsideration on the merits for the renewed petition under 37 CFR § 1.182 filed on September 16, 2004.

Appl. No.: 10/707,968

Renewed Petition under 37 CFR 1.182, dated November 12, 2004

Response to Decision of September 21, 2004

In the Decision, the Examiner stated that the Office would only grant petitions for the requested conversion upon showing by Applicants of sufficient cause (e.g., loss of patent rights) where no other remedy is available. The Examiner stated that Applicants have the ability to make the current 35 U.S.C. 111(a) application a continuation of the international application, which would cause no loss of patent rights. Since such remedy is available to Applicants, the renewed petition was not granted.

Applicants respectfully disagree. Such remedy is not available to Applicants. To obtain the benefit under 35 U.S.C. 120 and 365(c) of a prior international application, the continuing application must include a specific reference to the prior international application, either in the application data sheet or in the first sentence of the specification. See MPEP 1895.01(A). The specific reference must identify the parent international application by its international application number, international filing date and the relationship of the applications. See 37 CFR 1.78(a)(2)(i) and MPEP §201.11. The required reference must be submitted within the time period provided by 37 CFR 1.78(a)(5)(ii), which is within four months from the actual filing date of the present application. This time period is not extendable.

Although the reference contained in the Application Data Sheet (see Exhibit A, element a) and the first sentence of the originally filed specification (see Exhibit B, element b) identified the parent international application by its international application number and filing date, it does not state that the present application is a continuation of the international application. Since the time period for providing the required reference expired on May 29, 2004, Applicants do not have the opportunity to amend the reference to make the current 35 U.S.C. 111(a) application a continuation of the international application.

Appl. No.: 10/707,968

Renewed Petition under 37 CFR 1.182, dated November 12, 2004

Response to Decision of September 21, 2004

Applicants therefore submit that no other remedy is available in the present case.

Failure to grant this renewed petition would cause the Application to lose its priority date, resulting in Applicants' subsequent loss of patent rights. Therefore, sufficient cause is shown and no other remedy is available.

In view of the evidence presented, Applicants respectfully request that this renewed petition under 37 CFR 1.182 be granted, recognizing that US Application No. 10/707,968 is a national stage of PCT Application No. PCT/SG02/00174 under 35 U.S.C. §371. Issuance of a corrected formal filing receipt is respectfully requested and most appreciated.

Although Applicants do not believe that any fees are due, the Commissioner is nevertheless authorized to charge any additional fees that may be required, or credit any overpayment to Deposit Account No. 50-2388.

Dated: November 12, 2004

Respectfully submitted,

Dexter CHIN

Attorney for Applicants

Reg. No. 38,842

Horizon IP Pte Ltd 166 Kallang Way, 6th Floor Singapore 349249

Tel:

(65) 9836 9908

Fax:

(65) 6746 8263

US-Request

Exhibit A

APPLICATION DATA SHEET

Electronic Version v14 Stylesheet Version v14.0

Title of Invention

Gate Electrodes and the Formation Thereof

Application Type:

regular, utility

Attorney Docket Number: ASTAP2004-01

Correspondence address:

Customer Number:

031366

031366

а Continuing Data:

element

This is a National Stage of SG application number PCT/SG02/00174, filed 2002-07-31, now

Published.

Priority Data:

Doc.No: 0104614-3; Country - SG; Date: 2001-07-31 us-priority-claimed

Inventors Information:

Inventor 1:

Applicant Authority Type:

Inventor

Citizenship:

FR

Name prefix:

Mr.

Given Name:

Dominique

Family Name:

Mangelinck

City of Residence:

Marseille

Country of Residence:

FR

Address-1 of Mailing Address:

L2MP, UMR CNRS 6137, Case 151,

Address-2 of Mailing Address:

Faculte de St Jerome, Marseille Cedex 20, France 13397

City of Mailing Address:

Marseille

State of Mailing Address:

Postal Code of Mailing Address: 13397

Country of Mailing Address:

FR

Phone:

Fax:

Exhibit B

SPECIFICATION

[Electronic Version 1.2.8]

GATE ELECTRODES AND THE FORMATION THEREOF

element b

Cross Reference to Related Applications

This application is the National Stage of International Application No. PCT/SG02/00174, filed July 31, 2002, and which was published in English under PCT Article 21(2) as WO 03/012876 A1 on February 13, 2003. The International application claims priority to Singaporean Application No. 200104614-3, filed July 31, 2001.

Background of Invention

[0001] Referring to Figure 1 of the accompanying drawings, a complementary metal oxide semiconductor (CMOS) transistor comprises an n channel MOS (NMOS) and a p channel MOS (PMOS). Historically, a polycrystalline n+-Si gate is used as a gate electrode both in NMOS and PMOS transistors. For PMOS transistors additional boron Implantation into the channel region of the Si substrate is needed to control the threshold voltage because of the low work function of n+-Si. This can produce short channel effects and large sub-threshold currents and thus the PMOS transistor is less scaleable than the NMOS transistor. In order to solve this problem, a dual gate configuration where polycrystalline n+-Si and p+-Si are used as the gate for the NMOS and PMOS transistors, respectively, has been suggested. However, the dual gate CMOS has drawbacks, most notably boron penetration (for PMOS) through the gate oxide and the poly-depletion effect. Instead of using a dual gate, a material with a work function close to the value of the middle of the bandgap of siljcon (4.61 eV), can be used for both NMOS and PMOS transistors. A material with such a work function is called a midgap material and the process utilising this material for a gate electrode is known as mld-gap CMOS technology.

[0002] In addition, the contact surface of the gate electrode is actually provided by a silicide layer (TiSi₂, CoSi₂, PtSi₂, PtSi or NiSi) on top of the polycrystalline Si gate (e.g. n+-Si) in current CMOS fabrication processes. At relatively high temperatures (e.g. 600°C), the silicide film is usually degraded by two phenomena: inversion and agglomeration. Inversion is due to the grain growth of Si during the formation of